Notice of References Cited

Application/Control No. 10/708,009	Applicant(s)/Pater Reexamination CALDERONI ET	
Examiner	Art Unit	
Patricia A. George	1765	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-2004/0116080	06-2004	Chen et al.	455/115.1
	В	US-2004/0129218	07-2004	Takahashi et al.	118/715
	С	US-2004/0135590	07-2004	Quon, Bill H.	324/713
	D	US-2004/0055868	03-2004	O'Leary et al.	204/157.15
	Е	US-2003/0121609	07-2003	Ohmi et al.	156/345.47
	F	US-2005/0145334	07-2005	Parsons, Richard	156/345.24
	G	US-2004/0149384	08-2004	Kanno et al.	156/345.24
	H	US-2003/0227283	12-2003	Cox et al.	324/71.1
	ı	US-2002/0171454	11-2002	Yakabe et al.	327/77
	J	US-2002/0039887	04-2002	Delabbaye et al.	455/42
	К	US-5,925,212	07-1999	Rice et al.	156/345.27
	L	US-6,661,250	12-2003	Kim et al.	326/30
	М	US-6,756,790	06-2004	Yakabe et al.	324/649

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	JP 2003173973				
	0					
	Р					
	Q					
	R					,
	S					
	Т					•

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U/	Hanson et al. of Advanced Energy: Optimization Chemical Vapor Deposition Processing through RF Metrology, 1999
	V	Angra et al., Pramana _ Journal of Physics, Vol. 54, No.5, May 2000, pp.763-769: Unstable Plasma Charicteristics in Mirror / Field Electron Cyclotron Resonance, Microwave Ion Source
	w	
	x	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.